

Figure 1. Simulated particle size distribution at 84 cycles and Ru areal density at 1-167 cycles for EBECHRu ALD (325° C) on SiO₂-Si(CH₃)₃ and OSG surfaces. The green line denotes the equivalent Ru film thickness on a TiN growth surface.

Figure 2. Particle density on OSG non-growth surface area as a function of distance from the interface with the growth area.